

**FIG. 1**

**FIG. 2**

**THICKNESS OF CHEMICAL OXIDE FILM ON SILICON WAFER SURFACE (nm)**  
**TREATMENT TIME WITH OZONIZED WATER (sec)**

**FIG. 3**

**SC-1 CLEANING**

**OZONIZED WATER TREATMENT + HYDROFLUORIC ACID CLEANING**  
**EXISTENCE RATIO OF Si ATOM COORDINATION NUMBER (%)**  
**TIME PASSAGE SINCE CLEANING (hr)**

**FIG. 4**

**FIG. 5**

**HYDROGEN ANNEALING**  
**OZONIZED WATER/HF CLEANING**  
**SC-1 CLEANING**  
**SPATIAL FREQUENCY (/μm)**

**FIG. 6**

**HYDROGEN ANNEALING**  
**OZONIZED WATER CLEANING**  
**EXTRAPURE WATER CLEANING**  
**SPATIAL FREQUENCY (/μm)**

Fig. 1

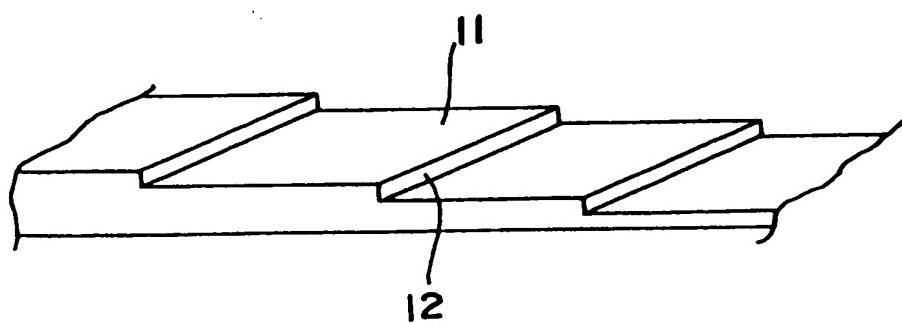


Fig.2

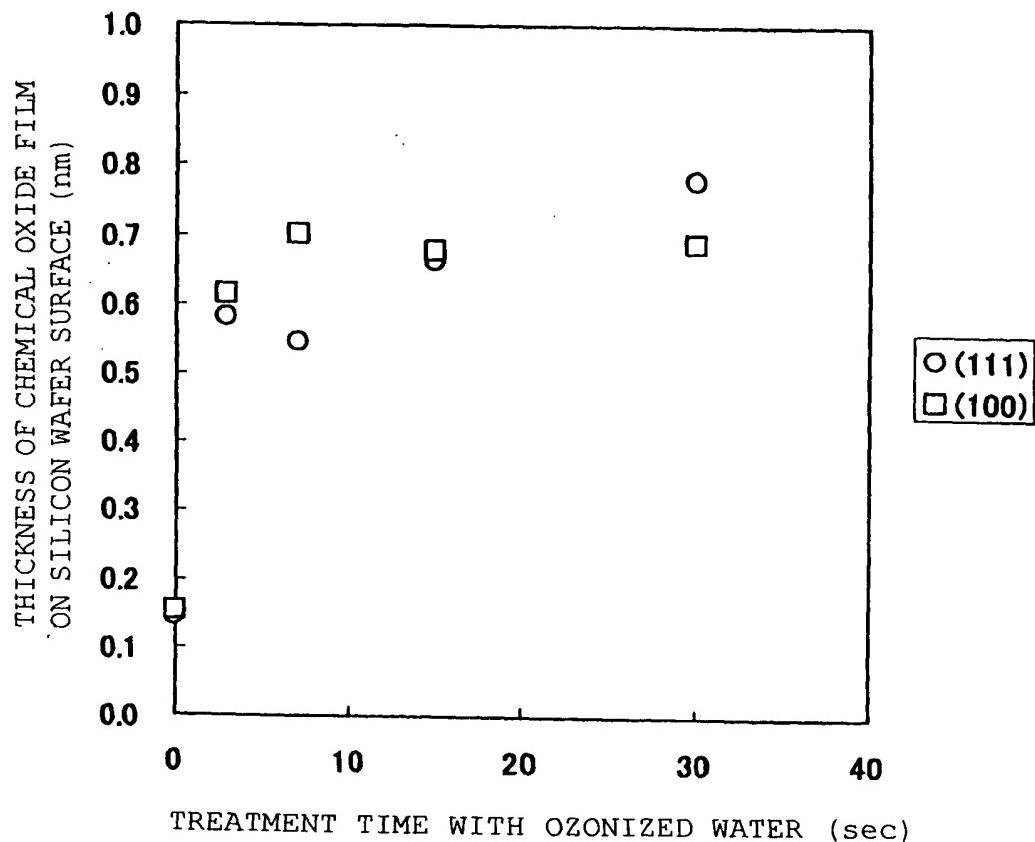


Fig. 3

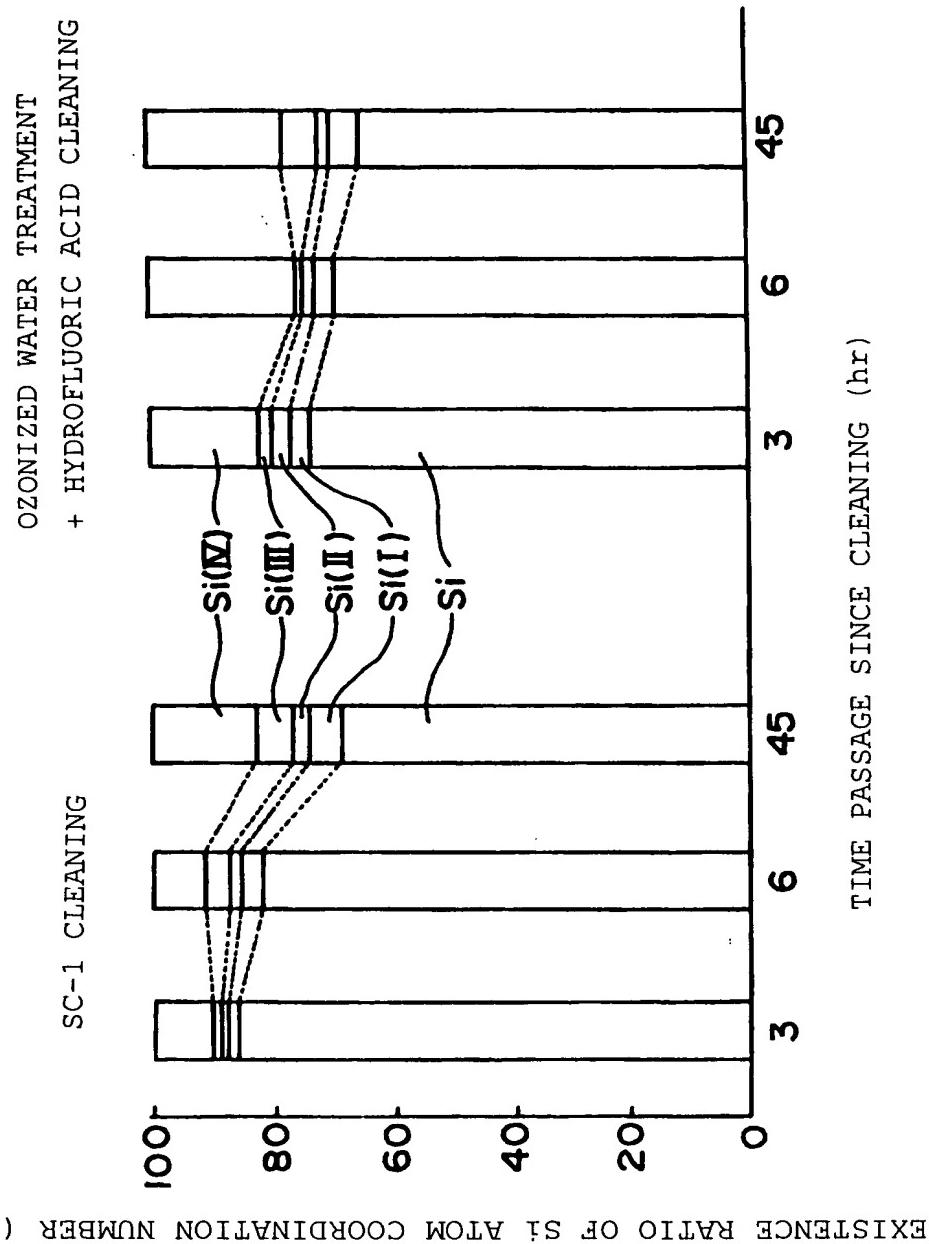


Fig. 4

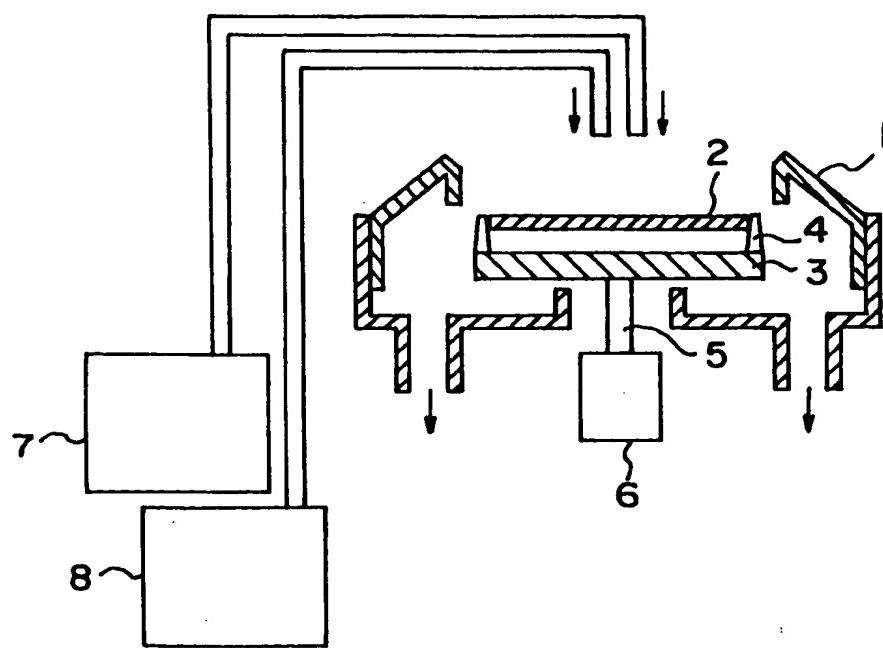


Fig.5

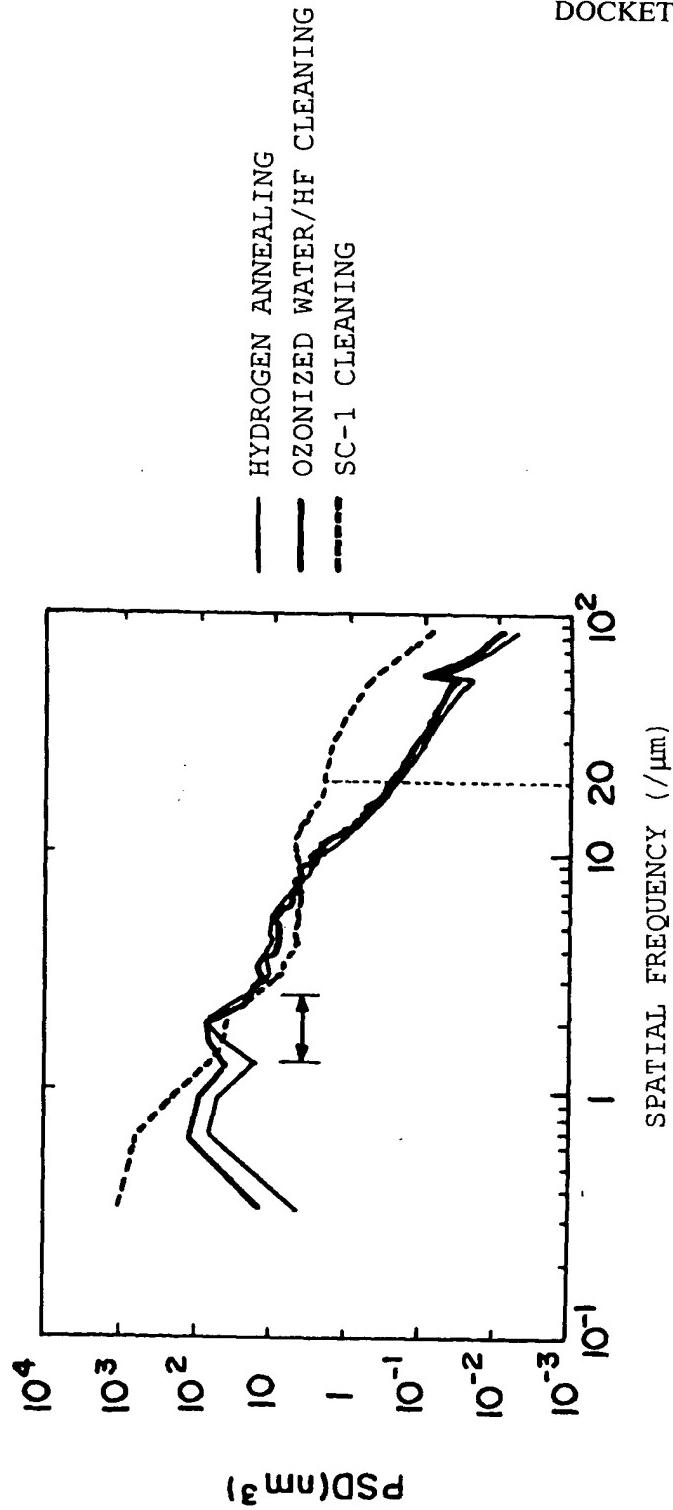


Fig. 6

